	Application No.	Applicant(s)
Nation of Allowskiller	10/694,053	UNNO ET AL.
Notice of Allowability	Examiner	Art Unit
	Michael S. Lebentritt	2824
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apportance or other appropriate communication GHTS. This application is subject to	plication. If not included will be mailed in due course. THIS
1. This communication is responsive to		
2. The allowed claim(s) is/are <u>5-8</u> .		
3. $\boxtimes$ The drawings filed on <u>28 October 2003</u> are accepted by the	e Examiner.	
<ul> <li>4.</li></ul>	been received.  been received in Application No. 10 cuments have been received in this of this communication to file a reply ENT of this application.  itted. Note the attached EXAMINER as reason(s) why the oath or declara t be submitted. on's Patent Drawing Review (PTO- as Amendment / Comment or in the Comment or in the Comment of BIOLOGICAL MATERIAL re-	complying with the requirements  'S AMENDMENT or NOTICE OF tion is deficient.  948) attached  Office action of the back) of d).  must be submitted. Note the
<ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/06 Paper No./Mail Date</li></ul>	6.  Interview Summary Paper No./Mail Dat 8), 7.  Examiner's Amendr 8.  Examiner's Stateme 9.  Other	te

## **REASONS FOR ALLOWANCE**

The following is an examiner's statement of reasons for allowance: prior art references fail to either singularly or in combination teach: forming a crystal layer of a crystalline insulative material on a silicon substrate heated up to not lower than 400°C; and forming an insulative silicon compound layer on said the silicon substrate by oxygen diffusion from an oxide during said forming step, oxygen diffusion during a temperature holding time after said ' forming step and/or oxygen diffusion during a cooling operation as specified in claim 4.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael S. Lebentritt whose telephone number is 571-272-1873. The examiner can normally be reached on 5/4/9.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Richard Elms can be reached on 571-272-1869. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Michael S. Lebentritt Primary Examiner Art Unit 2824

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